

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : **63-042050**

(43)Date of publication of application : **23.02.1988**

(51)Int.Cl.

**G11B 7/26**

**G11B 11/10**

(21)Application number : **61-185569**

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(22)Date of filing : **07.08.1986**

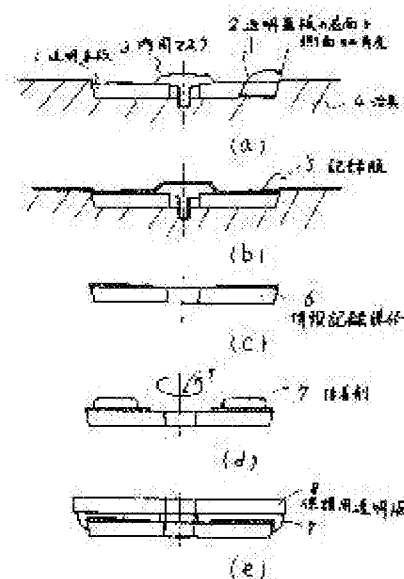
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## (54) MANUFACTURE OF INFORMATION RECORDING MEDIUM

### (57)Abstract:

**PURPOSE:** To prevent moisture or the like from penetrating an information recording part by sticking the recording film of an information recording substrate and a protective transparent plate to each other with an adhesive and coating the recording film with the adhesive to isolate it from the outside atmosphere.

**CONSTITUTION:** The center hole of a transparent substrate 1 where an angle 2 formed between the bottom face and the side face is  $90^\circ$  to  $135^\circ$  is used to attach this transparent substrate 1 to a jig 4 having a recessed part, which has the same diameter as the transparent substrate 1 and has a depth equal to or deeper than the transparent substrate so that the transparent substrate is fitted to the recessed part, together with an inner peripheral mask 3, and this jig 4 is set to a sputtering device. A recording film 5 is formed by sputtering, and the substrate 1 is detached from the jig 4 to obtain an information recording substrate 6. This substrate 6 is coated with an adhesive 7 while being rotated in the direction of an arrow 9, and a protective transparent plate 8 slightly larger than the information recording substrate 6 is put on the substrate 6 in vacuum, and the air pressure is restored to stick the plate 8. Thus, impurities, especially, moisture in the outside atmosphere is prevented from penetrating the information recording part.



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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